Docket No.: 5918/FPS/MMCS/APC/DV

PATENT/OFFICIAL

#### IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re Application of

SHANMUGASUNDRAM et al.

Serial No. 09/943,955

Group Art Unit: 2122

SEP 2 0 2002

Filed: August 31, 2001

Examiner:

**Technology Center 2100** 

For:

FEEDBACK CONTROL OF A CHEMICAL MECHANICAL POLISHING DEVICE

PROVIDING MANIPULATION OF REMOVAL RATE PROFILES

### SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

## Serial No. 09/943,955

to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

HALE AND DORR LLP

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Date: 9/19/02

SHEET 1 OF 4

Technology Center 2100

# INFORMATION DISCLOSURE CITATION IN AN **APPLICATION** (PTO-1449)

ATTY, DOCKET NO. SERIAL NO. 09/94 PECEIVED 5918/FPS/MMCS/APC/DV SEP 2 0 2002

APPLICANT SHANMUGASUNDRAM et al.

FILING DATE 2122 August 31, 2001

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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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CITATION IN AN ADDITION OF ADD SHEET 3 OF 4 ATTY. DOCKET NO. SERIAL NO. 5918/FPS/MMCS/APC/DV 09/943,955 RECEIVED SEP 2 0 2002 (PTO-1449) Technology Center 2100 APPLICANT SHANMUGASUNDRAM et al. FILING DATE GROUP August 31, 2001 2122 U.S. PATENT DOCUMENTS **EXAMINER'S** FILING DATE PATENT NO. **INITIALS** DATE NAME CLASS SUBCLASS 6,175,777 01/16/01 Kim 01/16/98 6,178,390 01/23/01 Jun 09/08/98 6,185,324 02/06/01 Ishihara et al. 01/31/95 6,192,291 02/20/01 Kwon 10/08/98 6,197,604 03/06/01 Miller et al. 10/01/98 6,211,094 04/03/01 Jun et al. 08/23/99 6,226,792 05/01/01 Goiffon et al. 10/14/98 6,230,069 05/08/01 Campbell et al. 06/26/98 05/22/01 6,236,903 Kim et al. 09/25/98 6,240,330 05/29/01 Kurtzberg et al. 05/28/97 FOREIGN PATENT DOCUMENTS COUNTRY **EXAMINER'S** PATENT NO. DATE CLASS SUBCLASS Translation INITIALS Yes No 05/21/99 11-135601 Japan X WO 00/05759 5 02/03/00 wo X WO 00/35063 . 06/15/00 wo X OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) July 5, 2001. "Motorola and Advanced Micro Devices Buy ObjectSpace Catalyst Advanced Process Control Product for Five Wafer Fabs." Semiconductor FABTECH. www.semiconductorfabtech.com/industry.news/9907/20.07.shtml October 15, 2001. Search Report prepared by the Austrian Patent Office for Singapore Patent Application No. 200004286-1. Johnson, Bob. June 10, 2002. "Advanced Process Control Key to Moore's Law." Gartner, Inc. July 9, 2002. International Search Report prepared by the European Patent Office for PCT/US01/24910.4 July 29, 2002. International Search Report prepared by the European Patent Office for PCT/US01/27407. Sonderman, Thomas. 2002. "APC as a Competitive Manufacturing Technology; AMD's Vision for 300mm." AEC/APC. **EXAMINER** DATE CONSIDERED

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